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(71) Applicant (for all designated States except US):
CYMER, INC. [US/US]; (a Nevada Corporation), 17075
Thornmint Court, San Diego, CA 92127-2413 (US).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **FOMENKOV, Igor, V.** [US/US]; 14390 Janal Way, San Diego, CA 92129 (US). **PARTLO, William, N.** [US/US]; 12634 Pedriza Drive, Poway, CA 92064 (US).

(74) Agent: **NGUYEN, Joseph, A.**; Cymer, Inc., Legal Dept., MS/4-2D, 17075 Thornmint Court, San Diego, CA 92127-2413 (US).

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(54) Title: SYSTEMS AND METHOD FOR TARGET MATERIAL DELIVERY PROTECTION IN A LASER PRODUCED PLASMA EUV LIGHT SOURCE

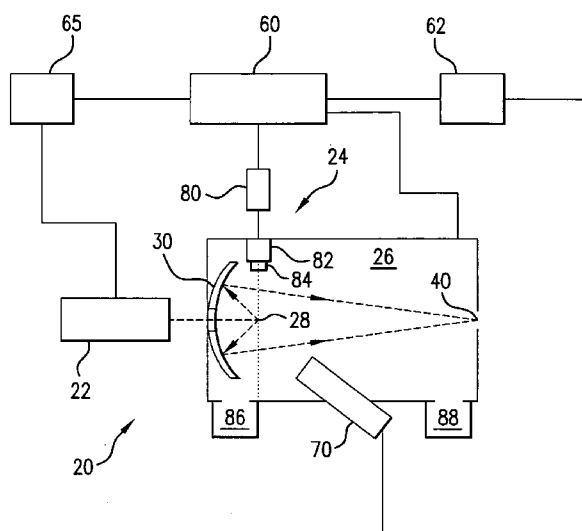


FIG.1

(57) Abstract: A device is disclosed herein which may comprise a chamber, a source providing a stream of target material droplets delivering target material to an irradiation region in the chamber along a path between a target material release point and the irradiation region, a gas flow in the chamber, at least a portion of the gas flowing in a direction toward the droplet stream, a system producing a laser beam irradiating droplets at the irradiation region to generate a plasma producing EUV radiation, and a shroud positioned along a portion of said stream, said shroud having a first shroud portion shielding droplets from said flow and an opposed open portion.